VISION INSPECTION APPARATUS AND VISION INSPECTION METHOD THEREFOR

ABSTRACT

A vision inspection apparatus for a semiconductor device, particularly, a vision inspection apparatus for a semiconductor device capable of inspecting a status of a semiconductor device by capturing external image of the semiconductor device, and then by analyzing the captured external image, the vision inspection apparatus for a semiconductor device including a two-dimensional vision inspection unit including a two-dimensional light source for irradiating light onto an inspection surface of one surface of an upper and a lower surfaces of one or more semiconductor devices to be inspected, and a two-dimensional camera for capturing image of the semiconductor device so as to obtain a two-dimensional shape by photographing inspection surface onto which the light from the two-dimensional light source has been irradiated; and a three-dimensional vision inspection unit including a three-dimensional light source for irradiating light onto the inspection surface inspected by the two-dimensional vision inspection unit, and a three-dimensional camera for capturing image of the semiconductor device so as to obtain a three-dimensional shape by photographing the inspection surface onto which the light from the three-dimensional light source has been irradiated, is disclosed.

Fig. 1